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## Microwave Applications in Chemical Engineering

Guest Editors:

**Prof. Dr. Kama Huang**

College of Electronics and  
Information Engineering, Sichuan  
University, Wangjiang Road 29,  
Chengdu, China

**Prof. Dr. Junwu Tao**

LAPLACE Laboratory, Toulouse  
INP-ENSEEIH, University of  
Toulouse, 31071 Toulouse,  
France

**Dr. Huacheng Zhu**

College of Electronics and  
Information Engineering, Sichuan  
University, Wangjiang Road 29,  
Chengdu, China

### Message from the Guest Editors

This Special Issue on “Microwave Applications in Chemical Engineering” aims at showing the most recent advances in dielectric properties measurement, microwave material interaction, industrial applications of microwave energy, modelling of microwave power applications, microwave plasma applications, microwave chemistry, microwave assisted biomass and waste processing, medical and biological applications of microwave, microwave processing design and optimization, and microwave assisted preparation of new materials.

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# Special Issue



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## Editor-in-Chief

**Prof. Dr. Giancarlo Cravotto**

Department of Drug Science and  
Technology, University of Turin,  
Via P. Giuria 9, 10125 Turin, Italy

## Message from the Editor-in-Chief

*Processes* (ISSN 2227-9717) provides an advanced forum for process/system-related research in chemistry, biology, material, energy, environment, food, pharmaceutical, manufacturing and allied engineering fields. The journal publishes regular research papers, communications, letters, short notes and reviews. Our aim is to encourage researchers to publish their experimental, theoretical and computational results in as much detail as necessary. There is no restriction on paper length or number of figures and tables.

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Processes Editorial Office  
MDPI, St. Alban-Anlage 66  
4052 Basel, Switzerland

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